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SIXTH SEMESTER B.TECH. (ENGINEERING) DEG EXAMINATION, APRIL 2014

(2009 Scheme)

EC/PTEC 09 601-VLSI DESIGN

(Regular/Supplementary/Improvement)

Time: Three Hours

Maximum: 70 Marks

## Part A

Answer all questions.
Each question carries 2 marks.

- 1. What is Channel length modulation?
- 2. Distinguish between depletion mode and enhancement mode MOSFET.
- 3. What is fault model? Give an example.
- 4. What is a contrast curve? Give its significance in VLSI fabrication.
- 5. What is a stick diagram?

 $(5 \times 2 = 10 \text{ marks})$ 

## Part B

Answer any four questions. Each question carries 5 marks.

- 6. Explain Pseudo NMOS logic.
- 7. Compare Static and Dynamic CMOS logic styles.
- 8. With neat sketch, explain the operation of a SRAM.
- 9. Explain Oxidation.
- 10. Explain twin tub process.
- 11. Draw the Layout of a two input CMOS NAND gate.

 $(4 \times 5 = 20 \text{ marks})$ 

## Part C

## Answer all questions.

- 12. (a) Explain:
  - (i) Drain induced barrier lowering.
  - (ii) Velocity saturation.

Or

(b) Explain the operation of a CMOS inverter and derive an expression for its propagation delay.

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- 13. (a) (i) With schematic explain the operation of a Carry bypass adder.
  - (ii) Design a pass transistor based 4 × 1 multiplexer.

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- (b) Explain any one test generation method with a suitable example.
- 14. (a) Explain diffusion, Oxidation and Ion Implantation.

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- (b) (i) Explain Optical lithography.
  - (ii) Explain MOCVD technique.
- 15. (a) Explain LOCOS, SILO and SWAMI process.

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(b) Explain λ based design rules.

 $(4 \times 10 = 40 \text{ marks})$